## IN THE CLAIMS:

Please amend the claims as shown in the following claim listing.

## **CLAIM LISTING:**

- 1. (Original) A process to produce a predictive data set which can be used to predict the property of a plating solution, said process comprising:
- (a) obtaining a sample set, wherein each sample comprises a plating solution of good performance;
- (b) obtaining an electroanalytical response for each said sample to produce a electroanalytical response data set;
- (c) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
- (d) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set; and
- (e) validating said training data set to produce said predictive data set for a predictive model.
- 2. (Original) A process of claim 1 wherein said property is selected from the group consisting of:

a concentration of individual component of said electroplating bath; an amount of breakdown products accumulated in said electroplating bath; an amount of foreign contaminants accumulated in said electroplating bath; a temperature of said electroplating bath; a quantity of hysteresis on recorded voltammogram;

or combinations thereof.

- 3. (Original) A process of claim 1, wherein said property comprises an overall plating performance.
- 4. (Original) A process of claim 3, wherein said overall plating performance is selected from the group consisting of:

throwing power;
brightness of the deposit;
tensile strengths of the deposit;
ductility of the deposit;
internal stress of the deposit;
solderability performance;
resistance to thermal shock;
uniformity of the deposit;
capability of uniform filling through holes;
capability of filling submicron features in a substrate surface;
or combinations thereof.

- 5. (Original) A process according to claim 1, wherein said plating solution is an electroplating bath.
- 6. (Currently Amended) A process of claim 5, wherein said electroplating bath comprises a plating bath of one or <u>more</u> metals selected from the following group <u>consisting of</u>: Cu, Sn, Pb, Zn, Ni, Ag, Cd, Co, Cr, and/or their alloys.

- 7. (Original) A process according to claim 1, wherein said plating solution is an electroless plating bath.
- 8. (Currently Amended) A process of claim 7, wherein said electroless plating bath comprises an autocatalytic plating bath of one or <u>more</u> metals selected from the following group consisting of: Cu, Sn, Pb, Ni, Ag, Au, and/or their alloys.
- 9. (Currently Amended) A process of claim 7, wherein said electroless plating bath comprises an immersion plating bath of one or <u>more</u> metals selected from the following group <u>consisting of</u>: Cu, Sn, Pb, Ni, Ag, Au and/or their alloys.
- 10. (Original) A process according to claim 1, wherein said plating solution is selected from the group consisting of:

an electrowinning bath;
an electrorefining bath;
an electropolishing bath;
an electroforming bath; or
an electromicromachining bath.

- 11. (Currently Amended) A process of claims 10, wherein said electroplating bath comprises a plating bath of one or <u>more</u> metals selected from the following group consisting of: Cu, Sn, Pb, Zn, Ni, Ag, Cd, Co, Cr, and/or their alloys.
- 12. (Original) A process of claim 1, wherein the sample set of step (a) comprises plating solutions of known concentration within specification range.

- 13. (Original) A process according to claim 1, wherein the sample data set of step (a) is obtained by design of experiment (DOE) routines.
- 14. (Original) A process according to claim 13, wherein said DOE routine is multicomponent multilevel linear orthogonal array.
- 15. (Original) A process according to claim 13, wherein said DOE routine is multicomponent multilevel fractional factorial.
- 16. (Original) A process of claim 1, wherein the sample set of step (a) comprises freshly prepared electroplating solutions of known concentration within specification range.
- 17. (Currently Amended) A process of claim 1, wherein said sample set of step (a) comprises industrial plating solutions with well <u>known</u> performance, <u>an</u> [[(]] empirical sample set [[)]].
- 18. (Currently Amended) A process to produce a predictive data set which can be used to predict the property of a plating solution, said process comprising:
- (a) obtaining a sample set, wherein each sample comprises a plating solution of good performance;
- (b) obtaining an electroanalytical response for each said sample to produce a electroanalytical response data set;
- (c) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
- (d) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set; and

(e) validating said training data set to produce said predictive data set for a predictive model

## A process according to claim 1

, wherein the electroanalytical response of step (b) is obtained by DC Voltammetry.

- 19. (Original) A process of claim 18, wherein the DC Voltammetry comprises DC cyclic Voltammetry.
- 20. (Original) A process of claim 18, wherein the DC Voltammetry comprises DC Linear Scan Voltammetry.
- 21. (Original) A process of claim 18, wherein the DC Voltammetry comprises DC Anodic Stripping Voltammetry.
- 22. (Original) A process of claim 18, wherein the DC Voltammetry comprises DC Cathodic Stripping Voltammetry.
- 23. (Original) A process of claim 18, wherein the DC Voltammetry comprises DC Adsorptive Stripping Voltammetry.
- 24. (Original) A process of claim 19, wherein the DC Voltammetry comprises DC Cyclic Voltammetric Stripping technique.
- 25. (Original) A process according to claim 1, wherein the electroanalytical response of step (b) is obtained by a technique selected from the group

## consisting of:

DC Staircase Voltammetry;

Normal Pulse Voltammetry;

Reverse Pulse Voltammetry;

Differential Pulse Voltammetry;

Square Wave Voltammetry;

AC Voltammetry;

Chronoamperometry;

Chronopotentiometry;

Electrochemical Impedance Spectroscopy technique;

Polarographic techniques;

or combinations thereof.

- 26. (Currently Amended) A process according to claim 1, wherein said electroanalytical response of step (b) comprises a plurality of data points.
- 27. (Original) A process according to claim 1, wherein said electroanalytical response of step (b) is a combination of one or more portions of a complete electroanalytical response.
- 28. (Original) A process according to claim 1, wherein said electroanalytical response of step (b) comprises a combination of one or more portions of independent electroanalytical responses.
- 29. (Original) A process of claim 1, wherein said decomposition method of step (d) is selected from the group of:

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Principal Component Analysis (PCA);
calculation of Mahalanobis Distance (MD);
calculation of Mahalanobis Distance with residuals (MDR);
calculation by Simple Modeling of Class Analogy (SIMCA);
calculation of F<sup>s</sup> ratio;
internal validation;
external validation;
and combinations thereof.
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- 30. (Currently Amended) A process to predict the property of said <u>a</u> plating solution, said process comprising:
  - (a) producing a predictive data set, the predictive data set generated by:
- (a1) obtaining a sample set, wherein each sample comprises an electrolyte solution of good performance;
- (a2) obtaining an electroanalytical response for each said sample to produce an electroanalytical response data set;
- (a3) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
  - (a4) preprocessing of said electroanalytical response data set;
- (a5) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set;
- (a6) validating said training data set to produce said predictive data set for a predictive model; and
- (b) using said predictive data set to predict the property of said plating solution, said property predicted by:

- (b1) obtaining an unknown sample set, wherein each unknown sample in said unknown sample set contains a plating solution;
- (b2) obtaining an electroanalytical response for each said unknown sample to produce an electroanalytical response data set;
  - (b3) preprocessing of said electroanalytical response data set; and
- (b4) applying said predictive model to predict property of each said unknown sample.
- 31. (Currently Amended) A process to detect faulty performance of said a plating solution, said process comprising:
  - (a) producing a predictive data set, the predictive data set generated by:
- (a1) obtaining a sample set, wherein each sample comprises an electrolyte solution of good performance;
- (a2) obtaining an electroanalytical response for each said sample to produce an electroanalytical response data set;
- (a3) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
  - (a4) preprocessing of said electroanalytical response data set;
- (a5) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set;
- (a6) validating said training data set to produce said predictive data set for a predictive model; and
- (a7) specifying the limits of good and faulty performance of said plating solution; and
  - (b) using said predictive data set to predict the property of said plating

solution and qualify said solution as correct or faulty said process comprises:

- (b1) obtaining an unknown sample set, wherein each unknown sample in said unknown sample set contains a plating solution;
- (b2) obtaining an electroanalytical response for each said unknown sample to produce an electroanalytical response data set;
  - (b3) preprocessing of said electroanalytical response data set;
- (b4) applying said predictive model to predict property of each said unknown sample; and
  - (b5) qualifying said unknown samples as correct or faulty.
- 32. (Currently Amended) A method of monitoring performance of plating solution in order to perform controlled feed and bleed procedure, said process comprising the steps of:
  - (a) producing a predictive data set, the predictive data set generated by:
- (a1) obtaining a sample set, wherein each sample comprises an electrolyte solution of good performance;
- (a2) obtaining an electroanalytical response for each said sample to produce an electroanalytical response data set;
- (a3) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
  - (a4) preprocessing of said electroanalytical response data set;
- (a5) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set;
- (a6) validating said training data set to produce said predictive data set for a predictive model;
  - (a7) defining the limits of said property for said plating solution that requires

feed and bleed procedure; and

- (b) using said predictive data set to predict the property of said plating solution and qualify said solution as correct or faulty said process comprises:
- (b1) obtaining an unknown sample set, wherein each unknown sample in said unknown sample set contains a plating solution;
- (b2) obtaining an electroanalytical response for each said unknown sample to produce an electroanalytical response data set;
  - (b3) preprocessing of said electroanalytical response data set;
- (b4) applying said predictive model to predict property of each said unknown sample; and
- (b5) qualifying said unknown samples as a ready or not ready solution for feed and bleed procedure.
- 33. (Currently Amended) A method of monitoring performance of electroplating solution in order to perform controlled purification treatment procedure, said process comprising the steps of:
  - (a) producing a predictive data set, the predictive data set generated by:
- (a1) obtaining a sample set, wherein each sample comprises an electrolyte solution of good performance;
- (a2) obtaining an electroanalytical response for each said sample to produce an electroanalytical response data set;
- (a3) obtaining a training set that comprises said sample set and corresponding said electroanalytical response data set;
  - (a4) preprocessing of said electroanalytical response data set;
- (a5) analyzing said training set using decomposition method coupled with discriminant analysis method to produce a discriminant parameters data set;

- (a6) validating said training data set to produce said predictive data set for a predictive model; and
- (a7) defining the limits of said property for said plating solution that requires purification treatment; and
- (b) using said predictive data set to predict the property of said plating solution and qualify said solution as correct or faulty said process comprises:
- (b1) obtaining an unknown sample set, wherein each unknown sample in said unknown sample set contains a plating solution;
- (b2) obtaining an electroanalytical response for each said unknown sample to produce an electroanalytical response data set;
  - (b3) preprocessing of said electroanalytical response data set;
- (b4) applying said predictive model to predict property of each said unknown sample; and
- (b5) qualifying said unknown samples as ready or not ready for purification treatment.
  - 34. (Cancelled).

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